

N THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Fabrice LETERTRE Confirmation No.: 6657

Application No.: 10/716,451 Group Art Unit: 1765

Examiner: Filing Date: November 20, 2003

METHOD OF FABRICATING Attorney Docket No.: For: 4717-11500

MONOCRYSTALLINE CRYSTALS

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

Sir:

Pursuant to Applicant's duty of disclosure under 37 C.F.R. § 1.56, enclosed is a Form PTO-1449 listing eleven (11) references for the Examiner's review. The references were cited in the Search Report for the corresponding French application, and a copy of the Search Report is enclosed.

Copies of non-U.S. patent references B1-B6 and C1-C5 are enclosed herewith. Copies of U.S. patent references A1-A3 will be provided if the Examiner so requests.

It is respectfully requested that the references be made of record in this application by the Examiner's completion and return of the attached Form PTO-1449.

This Information Disclosure Statement is filed under § 37 CFR 1.97(b)(3), before the mailing of a first Office Action on the merits. Thus, no fee is believed to be due. Should a fee be required, however, please charge such fee to Winston & Strawn LLP Deposit Account No. 50-1814.

Respectfully submitted,

il 26,2004

E. Bradley Gould

(Reg. No. 41,792)

Allah A. Fanucci

(Reg. No. 30,256)

WINSTON & STRAWN LLP

Customer No. 28765

202-371-5904

LIST OF REFERENCES CITED BY APPLICANT Form PTO-1449 (Vise several sheets if necessary)					ATTY. DOCKET NO.:	APPLICATION NO.: 10/716,451			
					4717-11500				
					APPLICANT:				
					Fabrice LETERTRE FILING DATE: GROUP:				
					November 20, 2003		1765		
			II C D	ATENT DO		· · · · · · · · · · · · · · · · · · ·	1703		
		TENT & TRACE.	0.5.1	ATENT DO	COMENTS		1	I	
*EXAMINER INITIAL	CITE NO.	DOCUMENT NUMBER	DATE	NAME		CLASS	SUBCLASS		PRIATE
	A1	6,328,796 B1	12/2001		Kub et al.	117	94		
	A2	2002/0096106	07/2002		Kub et al.	117	94		
	A3	2003/0036247	02/2003	Eriksen et al.		438	455		
			FOREIG	N PATENT	DOCUMENTS				
		DOCUMENT NUMBER	DATE		COUNTRY	CLASS	SUBCLASS	TRANSLATION	
		DOCUMENT NUMBER	DATE	COUNTRY		CLASS	JOBELASS	YES	NO
	B1	WO 96/41906	12/1996	PCT					
	B2	EP 0 961 312	01/1999	EPO					
	В3	WO 01/68957	09/2001	PCT					
	B4	JP 2001 253799	09/2001	Japan (with	English abstract)			X	
	B5	EP 1 245 702	02/2002	EPO					
	В6	JP 2003 183097	07/2003	Japan (with English abstract)				X	
		OTHER REFER	ENCES (Inc	cluding Autho	r, Title, Date, Pertinent	Pages, Etc.,)		
	C1				s in H ⁺ Implanted 6H-SiC tering B, Vol. 61-62, pp. 3			ı Carbi	ide on
	C2	Hugonnard-Bruyère, E., et al., "Defect Studies in Epitaxial SiC-6H Layers on Insulator (SiCOI)", Microelectronic Engineering, Vol. 48, pp. 277-280 (1999)							
	С3	Miller S.C. et al. "Progress in the Industrial Production of SiC Substrate for Semiconductor Devices"							
	C4	Tsvetkov, V. et al., "SiC Seeded Boule Growth", Materials Science Forum, Vols. 264-268, pp. 3-8 (1998)							
	C5	Tsvetkov, V.F. et al., "Recent Progress in SiC Crystal Growth", Inst. Phys. Conf. Ser., No. 142, Chap. 1, pp. 17-22 (1996)							
EXAMINER					DATE CONSIDERED				
EXAMINI	R·	Initial if reference consider	red whether or	not citation is in	conformance with MPEP 60	9. Draw line	through cits	tion if	not in